L Number	Hits	Search Text	T-22	<u>,                                     </u>
- Hanber	0	"20020157068"	DB	Time stamp
l _			USPAT	2004/05/06 11:19
	i i	"20020157068"	USPAT;	2004/05/06 15:34
	1	110500001011	US-PGPUB	•
-	1 1	"05206219"	JPO	2004/05/06 11:19
	. 472	(opc or optical near process near	USPAT;	2004/05/10 18:16
	ĺ	correction) and photolithography and mask	US-PGPUB;	<u>'</u>
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-	44		USPAT;	2004/05/06 16:01
		correction) and photolithography and mask)	US-PGPUB;	
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		or reticle near writ\$3 near (tool or	EPO; JPO;	
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<u> </u>	44	((opc or optical near process near	USPAT;	2004/05/06 16:03
		correction) and photolithography and (mask	US-PGPUB;	2004/03/00 10:03
		or reticle near writ\$3 near (tool or	EPO; JPO;	
· ·		device))) and hierarchy		
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	22	(((opc or optical near process near	USPAT;	2004/05/10 15:25
		correction) and photolithography and (mask	1	2004/05/10 15:25
		or reticle near writ\$3 near (tool or	US-PGPUB;	İ
	•	device))) and hierarchy) and (reduc\$3 or	EPO; JPO;	
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_	19	(((opc or optical near process near	IBM TOB	000.405450 55 55
	19	((tope of optical near process near	USPAT;	2004/05/10 15:26
		correction) and photolithography and (mask	JPO;	
		or reticle near writ\$3 near (tool or	DERWENT	
	*	device))) and hierarchy) and (reduc\$3 or	ŀ	
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	. 4	((((opc or optical near process near	USPAT;	2004/05/10 15:30
*	,	correction) and photolithography and (mask	JPO;	
		or reticle near writ\$3 near (tool or	DERWENT	
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ľ		correction) and photolithography and (mask	JPO;	÷
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		near correction) and photolithography and	US-PGPUB;	, , ,
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		near correction) and photolithography and	US-PGPUB;	===, 55, 15 15.1,
		mask	EPO; JPO;	
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